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JP9173053A2: YEAST VARIANT
HIGHLY SENSITIVE TO
IMMUNOSUPPRESSIVE AGENTS AND
ITS APPLICATION

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Country:

JP Japan

Kind:

Inventor(s):

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Applicant(s):

TONEN CORP

News, Profiles, Stocks and More about this company

Issued/Filed Dates:

July 8, 1997 / Dec. 27, 1995

Application Number:

JP1995000341819

IPC Class:

C12N 1/16; C12Q 1/02; C12N 1/16;

Abstract:

Problem to be solved: To obtain the subject new yeast variant comprising Saccharomyces cerevisiae, whose multiplication is suppressed by an immunosuppressive agent FK506 of a specific concentration, and which is used for determining effects of immunosuppressive agents as according the agents.

immunosuppressive agents or screening the agents. **Solution**: This new yeast variant highly sensitive to

immunosuppressive agents comprises SU3 strain (FERM P-15362) of Saccharomyces-cerevisiae whose multiplication is suppressed by $0.1 \mu g/ml$ of an immunosuppressive agent FK505, and useful as a reagent for determining effects of immunosuppressive agents or screening the agents. This yeast variant is obtained by using DV3T-A strain which is a malfunctioned variant of tonoplast, H+-ATPase, of Saccharomyces- cerevisiae as a parent strain, culturing the parent strain on a medium that contains ethylmethanesulfonic acid (EMS) as a mutagen to mutate the parent strain, screening the

living germs on a culture medium containing the

immunosuppressive agent FK506 in concentration of 0.1µg/l, and

selecting the multiplication- suppressed strain.

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Other Abstract Info:

none

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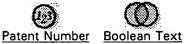
Foreign References:

(No patents reference this one)



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